

What is claimed is:

1. A substrate processing apparatus for processing a substrate with a plurality of processing solutions having different components, comprising:

5 a holding element provided on a rotating base, for holding a peripheral portion of a substrate to keep said substrate in a substantially-horizontal position;

 a rotation element for rotating said substrate held by said holding element about an axis along a substantially-vertical direction;

 an atmosphere cutoff plate positioned above said holding element, facing a top
10 surface of said substrate held by said holding element; and

 a splash prevention element for receiving said plurality of processing solutions splashed from said peripheral portion of said substrate held by said holding element,

 wherein said splash prevention element comprises

 a plurality of recovery ducts used for collecting said plurality of processing
15 solutions;

 a plurality of guiding members for forming said plurality of recovery ducts so that a vertical spacing of each opening thereof is not less than a distance between said rotating base and said atmosphere cutoff plate; and

 a selection element for selecting one of said recovery ducts to be used for
20 collecting a processing solution used in a processing for said substrate, to determine a selected recovery duct, and

 wherein a level of a top surface of a guiding member used for forming said selected recovery duct is set not higher than a level of a top surface of said atmosphere cutoff plate near an opening of said selected recovery duct.

2. A substrate processing apparatus for processing a substrate with a plurality of processing solutions having different components, comprising:

a holding element provided on a rotating base, for holding a peripheral portion of a substrate to keep said substrate in a substantially-horizontal position;

5 a rotation element for rotating said substrate held by said holding element about an axis along a substantially-vertical direction;

an atmosphere cutoff plate positioned above said holding element, facing a top surface of said substrate held by said holding element; and

a splash prevention element for receiving said plurality of processing solutions splashed from said peripheral portion of said substrate held by said holding element,

wherein said splash prevention element comprises

a plurality of recovery ducts used for collecting said plurality of processing solutions;

15 a plurality of guiding members for forming said plurality of recovery ducts so that a vertical spacing of each opening thereof is not less than a distance between said rotating base and said atmosphere cutoff plate; and

a selection element for selecting one of said recovery ducts to be used for collecting a processing solution used in a processing for said substrate, to determine a selected recovery duct, and

20 wherein a level of a lower surface of a guiding member used for forming said selected recovery duct is set not lower than a level of a lower surface of said rotating base near an opening of said selected recovery duct.

3. The substrate processing apparatus according to claim 2, wherein

25 a level of a top surface of a guiding member used for forming said selected

recovery duct is set not higher than a level of a top surface of said atmosphere cutoff plate.

4. The substrate processing apparatus according to claim 1, 2 or 3, wherein
5 said selected recovery duct has a shape curving downward, going away from a
substrate with a vertical spacing almost equal to a vertical spacing of an opening thereof.

5. The substrate processing apparatus according to claim 1, 2 or 3, wherein
 said selected recovery duct guides one of said plurality of processing solutions
10 downward almost around a substrate.

6. The substrate processing apparatus according to claim 1, 2 or 3, further
comprising
 a suck element communicated with said selected recovery duct, for sucking said
15 one of said plurality of processing solutions.

7. The substrate processing apparatus according to claim 1, 2 or 3, wherein
 said rotating base and said atmosphere cutoff plate each have a disk-like shape
and respective edge portions thereof facing said plurality of recovery ducts are vertical
20 side surfaces.

8. The substrate processing apparatus according to claim 1, 2 or 3, wherein
 respective openings of said plurality of recovery ducts which are vertically
stacked are disposed at almost the same position in a vertical direction.